

PATENT
Attorney's Docket No. 3521.125



ART UNIT: 2822

EXAMINER: Tonieae M. Thomas

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
ANDREW M. HAWRYLUK et al.)
Serial No.: 09/536,927)
Filed: March 27, 2000)

AMENDMENT DETAILS
OF AMENDMENT A

For: METHODS FOR ANNEALING A SUBSTRATE AND ARTICLE PRODUCED BY SUCH
METHODS

In the Claims:

Amend claims 58 and 59 as follows:

58. (Amended) A method as claimed in claim [53] 56 wherein the ions are implanted with an energy that produces a doped region in the substrate extending to a predetermined depth and the thermal energy imparted by the ions has a diffusion length, during the duration of the pulse, that is less than one-hundred (100) microns.

59. (Amended) A method as claimed in claim [53] 56 wherein the ions include at least one boron (B), aluminum (Al), gallium (Ga), indium (In), arsenic (As), phosphorus (P), and antimony (Sb).

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